

LISTING OF THE CLAIMS

This listing of claims will replace all prior versions, and listings, of claims in the application:

Claims 1 - 16 (Canceled)

Claim 17 (Currently Amended)

A substrate processing apparatus comprising:

~~a plurality of an alkaline developing units containing an alkaline developing solution for performing different an alkaline developing processes for a substrate, respectively;~~

an organic developing unit containing an organic developing solution for performing an organic developing process for a substrate;

a high-pressure processing unit for allowing a high-pressure fluid or a mixture of the high-pressure fluid and a chemical agent, as a processing fluid, to contact a surface of said developed substrate thereby performing a predetermined surface treatment for said developed substrate; and

a transport unit common to said plural developing units, capable of accessing said plural developing units and said high-pressure processing unit, for unloading the developed substrate from any one of said plural developing units and for loading said developed substrate into said high-pressure processing unit,

~~wherein at least one of said plural developing units is an alkaline developing unit for performing an alkaline developing process, and at least one of said plural developing units is an organic developing unit for performing an organic developing process;~~

wherein each of said plural developing units includes:

developing solution supply means for supplying a the corresponding said developing solution to said substrate;

rinse liquid supply means for supplying a rinse liquid to said substrate; and

replacing solution supply means for supplying a replacing solution having a composition which is different from that of said rinse liquid to said substrate thereby replacing said rinse liquid with said replacing solution;

wherein said plural developing units each perform a replacing process as a final processing of said developing process for replacing the solution ~~component~~ adhered to said substrate, with said replacing solution being common to said plural developing units.

Claim 18 (Original)

The substrate processing apparatus according to claim 17, wherein said transport unit wet-transport said developed substrate from any one of said plural developing units to said high-pressure processing unit.

Claim 19 (Original)

The substrate processing apparatus according to claim 17, comprising a plural number of said high-pressure processing units,

wherein said transport unit is capable of accessing said plural high-pressure processing units for unloading said developed substrate from any one of said plural developing units and for loading said developed substrate selectively to one of said plural high-pressure processing units.

Claim 20 (Canceled)

Claim 21 (Currently Amended)

A substrate processing apparatus comprising:

~~a plurality of~~ an alkaline developing units containing an alkaline developing solution for performing ~~different~~ an alkaline developing processes for a substrate, ~~respectively~~;

an organic developing unit containing an organic developing solution for performing an organic developing process for a substrate;

a replacing unit for replacing a solution component adhered to said developed substrate with a replacing solution;

a high-pressure processing unit for allowing a high-pressure fluid or a mixture of a high-pressure fluid and a chemical agent, as a processing fluid, to contact a surface of said substrate subjected to the replacing process thereby performing a predetermined surface treatment for said substrate subjected to the replacing process; and

a transport unit common to said plural developing units, capable of accessing said plural developing units, said replacing unit and said high-pressure processing unit, for unloading the developed substrate from any one of said plural developing units and for loading said developed substrate into said replacing unit and for unloading the substrate subjected to the replacing process from said replacing unit and for loading said substrate subjected to the replacing process into said high-pressure processing unit,

~~wherein at least one of said plural developing units is an alkaline developing unit for performing an alkaline developing process and at least one of said plural developing units is an organic developing unit for performing an organic developing process;~~

wherein each of said plural developing units includes:

developing solution supply means for supplying a the corresponding said developing solution to said substrate;

and

rinse liquid supply means for supplying a rinse liquid to said substrate,

wherein said replacing solution has a composition which is different from that of said rinse liquid; and

wherein said replacing unit performs a replacing process for replacing the solution ~~component~~ adhered to said substrate, with said replacing solution being common to said plural developing units.

Claim 22 (Previously Presented)

The substrate processing apparatus according to claim 21, wherein said transport unit wet-transportes said substrate among said plural developing units, said replacing unit and said high-pressure processing unit.

Claim 23 (Previously Presented)

The substrate processing apparatus according to claim 21, comprising a plural number of said high-pressure processing units,

wherein said transport unit is capable of accessing said plural high-pressure processing units for unloading said substrate subjected to the replacing process from said replacing unit and for loading said substrate selectively to one of said plural high-pressure processing units.

Claims 24-27 (Canceled)

Claim 28 (Previously Presented)

The substrate processing apparatus according to claim 17, wherein said replacing solution is liquid for preventing said substrate from becoming air-dry during the transportation of the substrate from any one of said plural developing units to said high-pressure processing unit.

Claim 29 (Previously Presented)

The substrate processing apparatus according to claim 21, wherein said replacing solution is liquid for preventing said substrate from becoming air-dry during the transportation of the substrate from said replacing unit to said high pressure processing unit.